Supplementary Information (SI) for Nanoscale Advances. This journal is © The Royal Society of Chemistry 2025

Supporting Information (SI)

Nguyen Xuan Sang^{1,2}, Khang D. Pham^{3,4,†}

¹Atomic Molecular and Optical Physics Research Group, Institute for Advanced Study in Technology, Ton Duc Thang University, Ho Chi Minh City, Vietnam. Email: nguyenxuansang@tdtu.edu.vn

²Faculty of Electrical and Electronics Engineering, Ton Duc Thang University, Ho Chi Minh City, Vietnam

³Institute of Research and Development, Duy Tan University, Da Nang 550000, Vietnam. E-mail: phamdinhkhang@duytan.edu.vn

⁴School of Engineering & Technology, Duy Tan University, Da Nang 550000, Vietnam

† To whom correspondence should be addressed

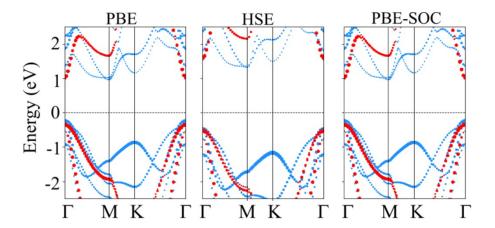


Fig. S1. Projected band structures of the GeH/SiSb heterostructure for the most favorable stacking pattern AB1 obtained by PBE, HSE and PBE-SOC methods.